EasyTube® 6000 Multi-Tube Horizontal Furnace System

Batch processing of multiple wafers in separately configured reactors all-in-one

The EasyTube® 6000 series multi-tube horizontal furnace systems are automatically controlled research units for batch processing of up to 50 wafers per run per tube (process dependent), in up to four separately configured process tubes.

Our ET6000 series systems are used for complementary metal oxide semiconductor (CMOS), photovoltaics (PV), micro electro mechanical systems (MEMS), and nano electro mechanical systems (NEMS) research to perform oxidation, annealing, diffusion, silicon oxide, and nitride deposition processes.

The systems are designed to meet today’s safety standards for handling pyrophoric, corrosive, flammable, and toxic gases such as hydrogen, silane, germane, diborane, hydrogen chloride, and metal organic precursors.

Mounting Choices
Standard left-hand as shown, optional right-hand, bulkhead, or ballroom.

Atmospheric or Low Pressure
Process tubes are individually configured for atmospheric and/or low pressure operation.

Cantilevered Loading System
Automatic cantilevered substrate loading mechanism with horizontal HEPA filtered laminar flow to minimize particle contamination during loading.

Cascade Temperature Control
Provides an accurate internal temperature profile with the responsiveness of external (furnace) temperature control. Each furnace is multi-zone for control of thermal profiles.

Innovative Modular Platform
Enables a wide range of options that can be configured to meet your specific processing requirements. Most system options are also available as upgrades after install.

powered by CVDWinPrC™

Operated through our CVDWinPrC™ process control software, the system automatically logs data and graphically shows time-dependent values of user-selected parameters. CVDWinPrC™ also allows users to load preprogrammed recipes, modify, check and create new recipes, and view realtime or saved process data.

Safety Protocols
The system has application-customized safety protocols embedded into relay logic, PLC, and our CVDWinPrC™ software.
FirstNano™ offers CVD processing systems with support equipment such as gas cabinets and exhaust gas conditioning systems. All major components from one vendor makes an easier and less costly system startup.

Call us at +1 631-981-7081 to discuss a product solution for your project. We can also be reached at sales@firstnano.com or visit our website.